

(19)  
(12)

(KR)  
(A)

(51) 。 Int. Cl. <sup>7</sup>  
H01L 21/76

(11)  
(43)

2002 - 0002943  
2002 01 10

(21) 10 - 2000 - 0037313  
(22) 2000 06 30

(71)

136 - 1

(72)

102 - 101

(74)

:

(54)

(Epitaxial)

(Trench)

(Seed)

가

3a

1a

1f

2

3a 3e

4

< >

31: 32:

33: 34:

(Epitaxial)

1a 1f , 2

(Shallow Trench Isolation : STI) , 1a ,  
 (11) (12) (13)

1b , (13) (14) , 2  
 (14)

1c , (14) (13), ( ,  
 12) (11) (Trench)(15) , (14)

1d , (15) (16)

, (16) , (15) (17)

1e , (13) (Etch Stopper) (16) CMP(Chem  
 ical Mechanical Polishing) (Etch Back) (15)

1f , (11) (13) 1 (12)

가

3a 3e , 4

(31) (32) STI , 3a ,

3b , (32) (Reverse tone) (33) , 4  
(33)

3c , (33) (33) (32)

3d , (32) (31)  
(34)

3e , (32) (34) CMP

(Seed)

가 가

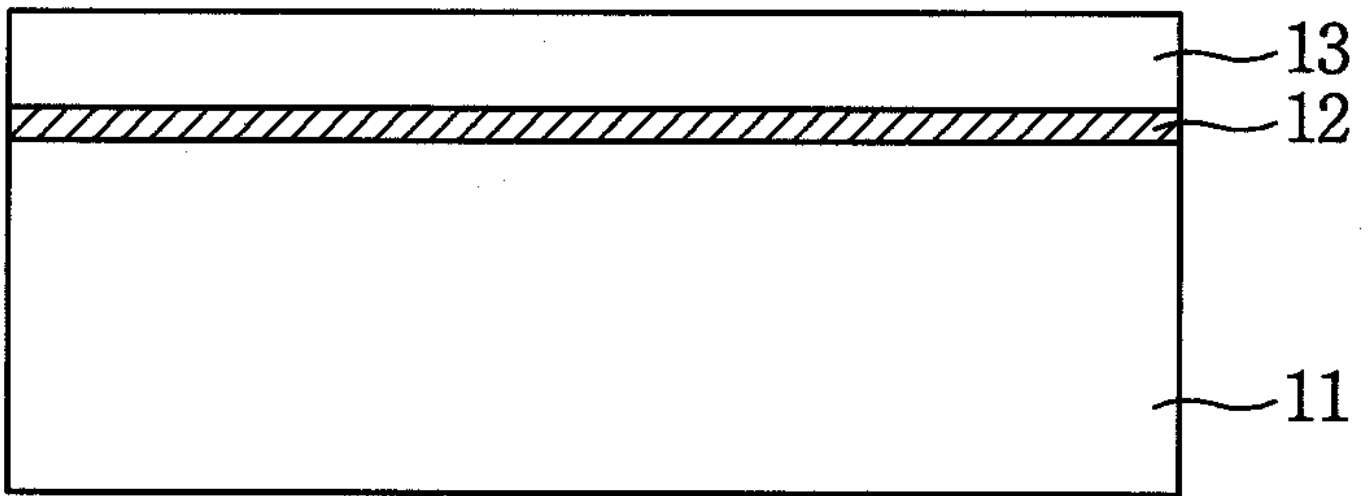
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1.

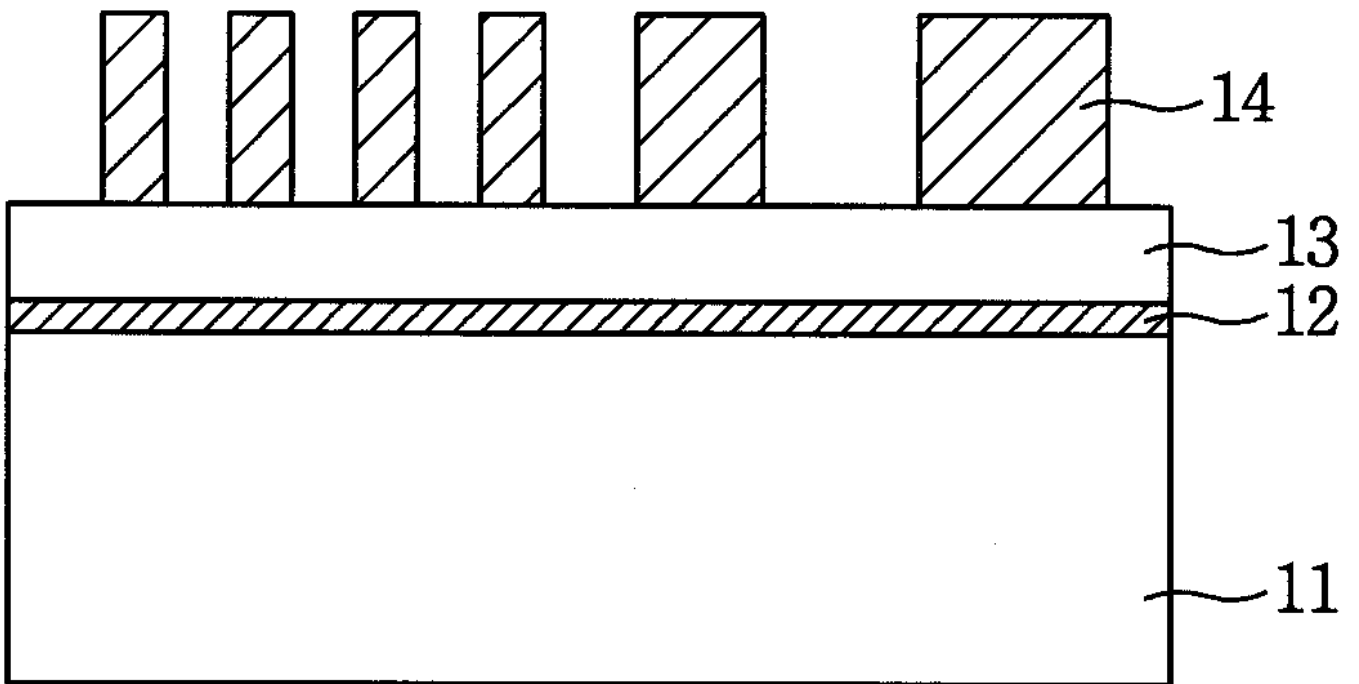
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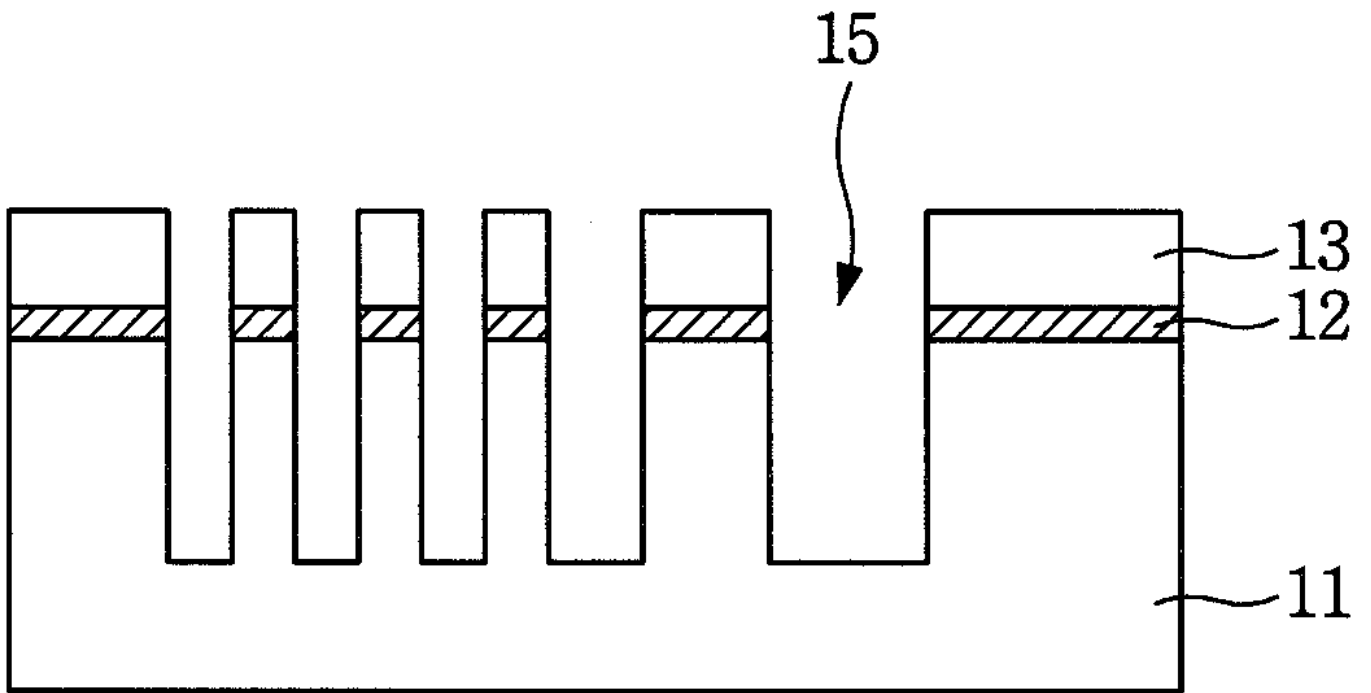
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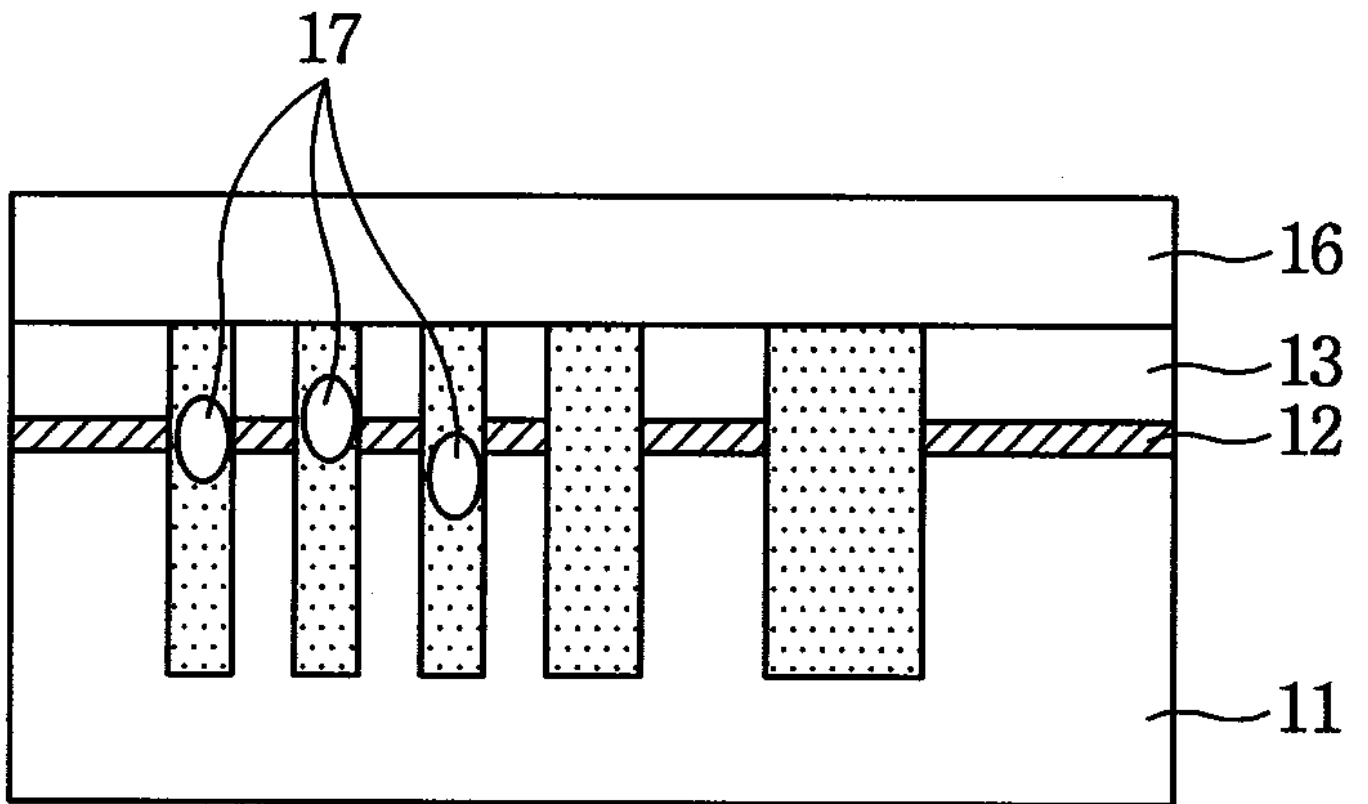
1b



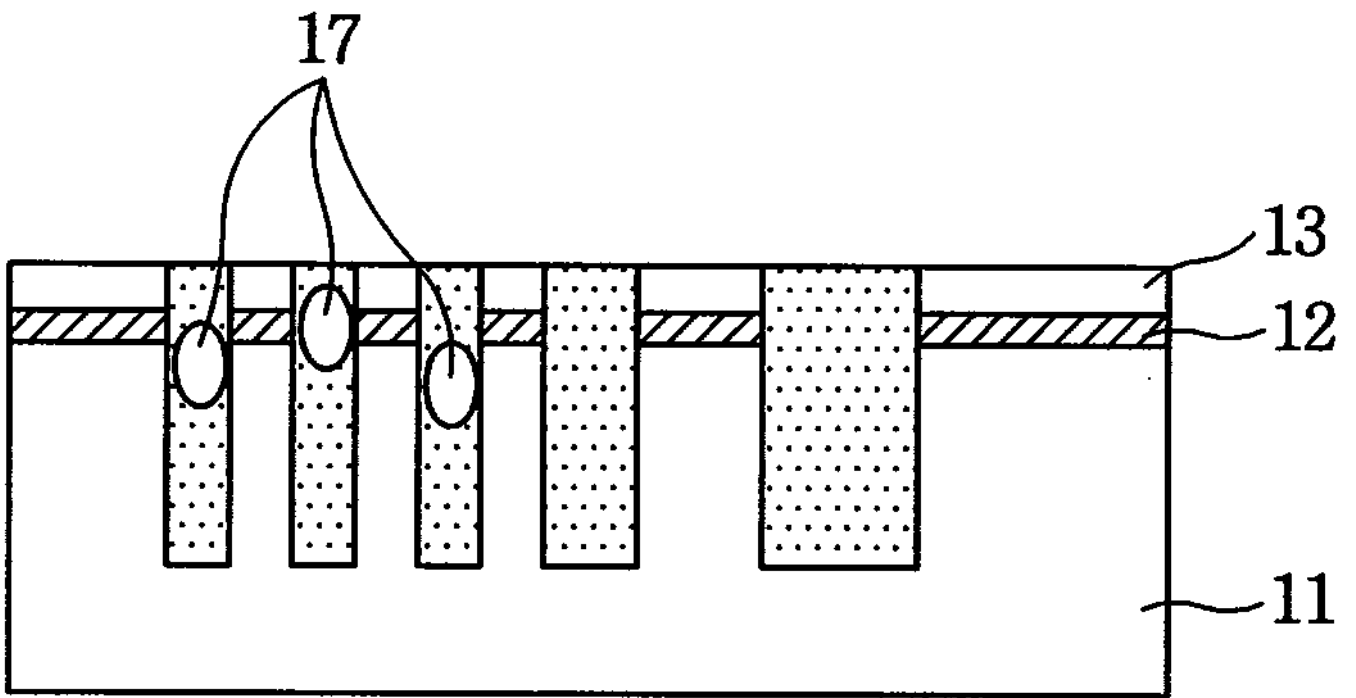
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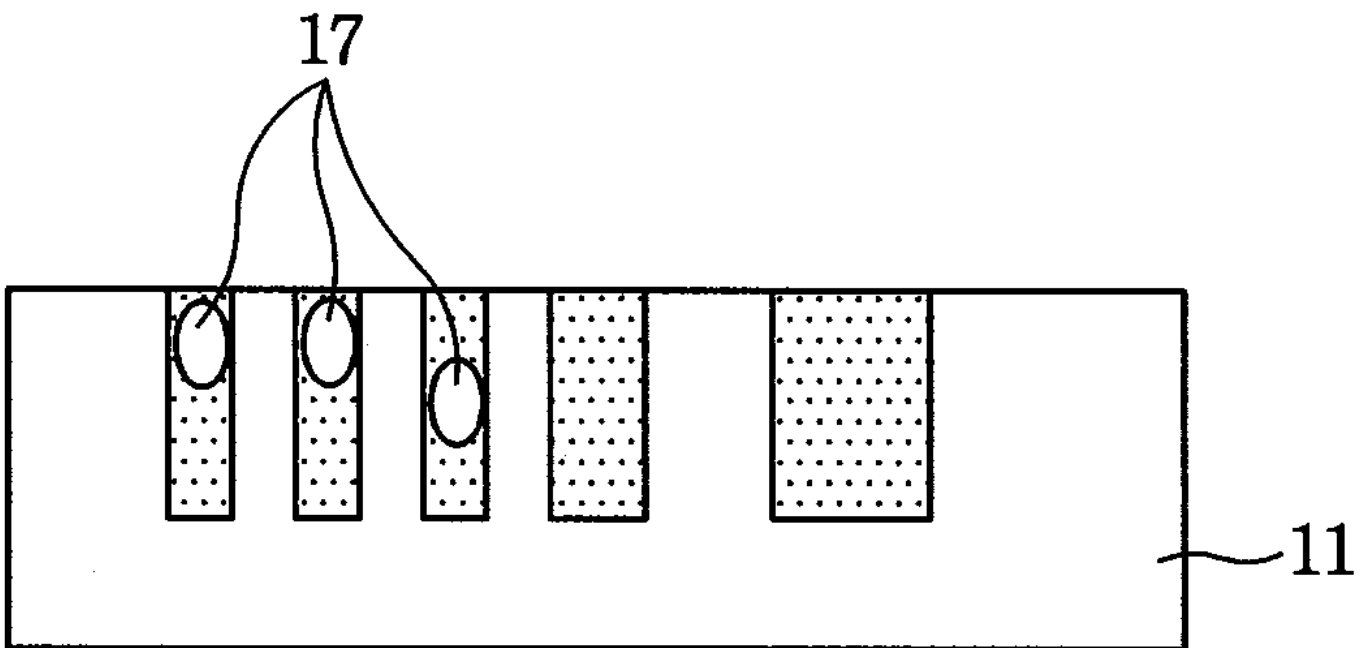
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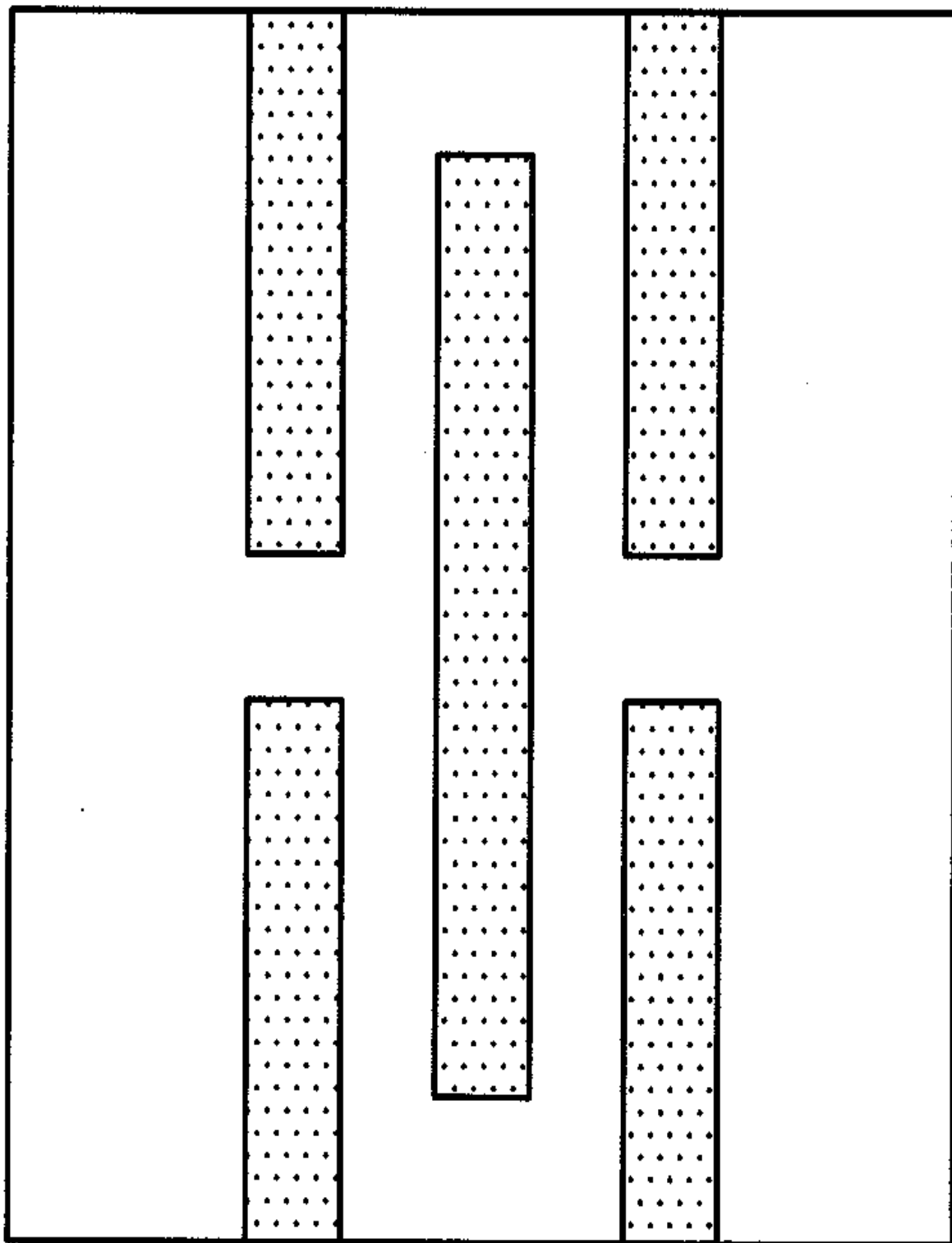


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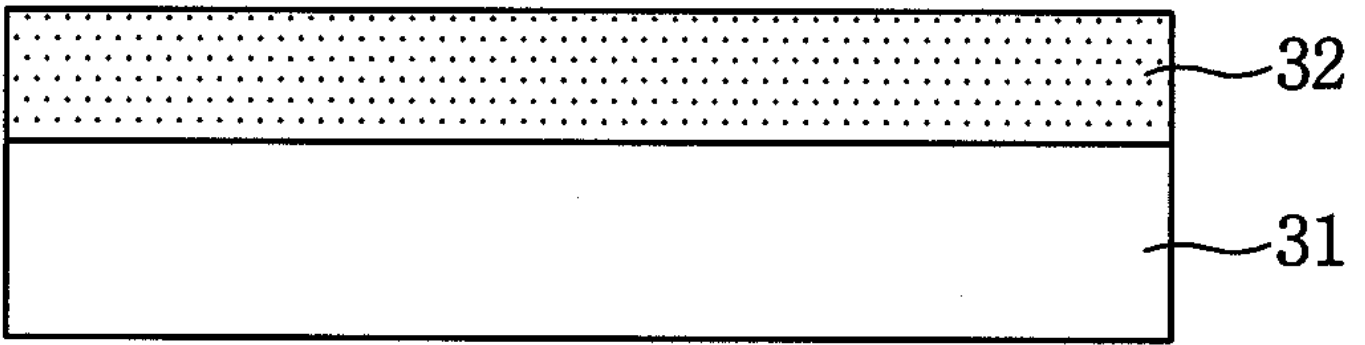


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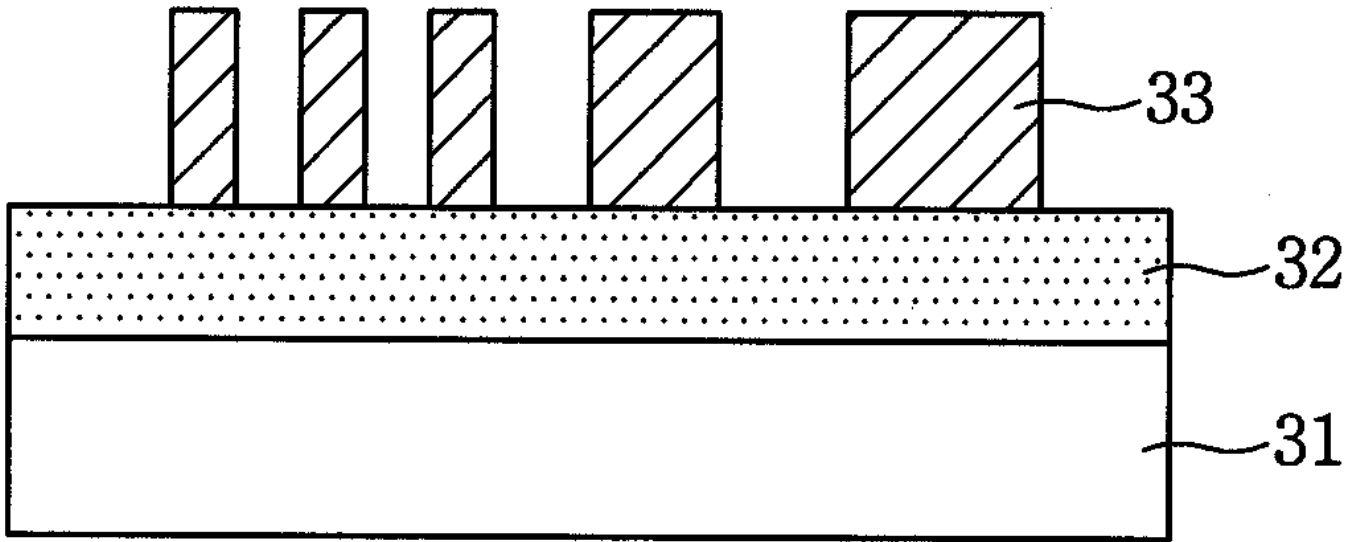




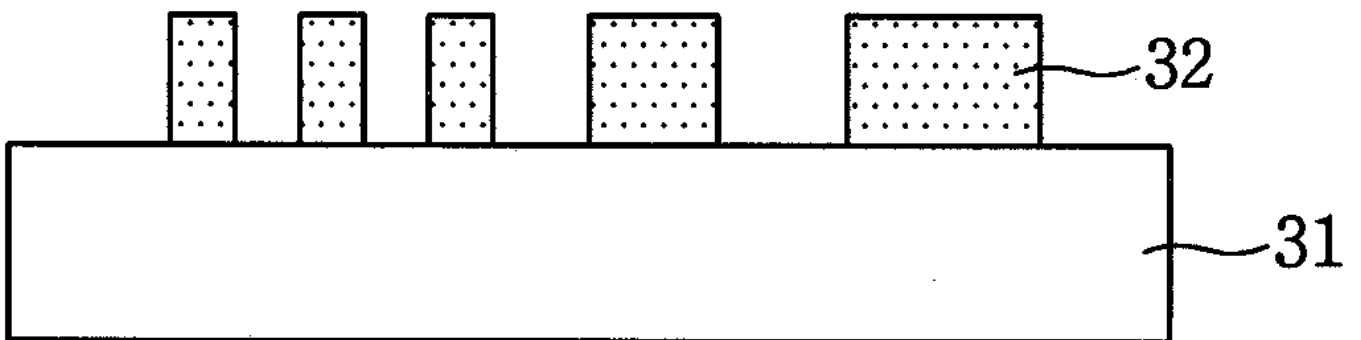
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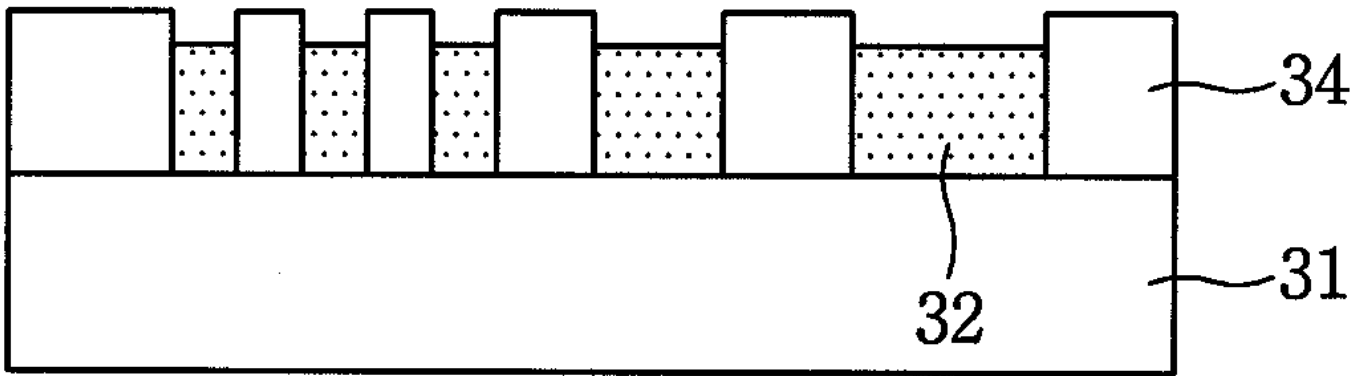
3b



3c



3d



3e

